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(54) PHOTORESIST RESIN COMPOSITION,
PHOTORESIST SHEET USING THE SAME
AND MANUFACTURING METHOD FOR
MOLDED PRODUCT

(57) Abstract:

PROBLEM TO BE SOLVED: To provide a photorestit sheet capable of being advantageously used in the production of a molded product having good design effect, excellent in abrasion resistance, weatherability

and chemical resistance, having no surface tackiness and excellent in processability and storage stability.

SOLUTION: A photorestit resin composition to be used contains (a-1) a thermoplastic resin having a photopolymerizable functional group in its side chain, (a-2) a photopolymerization initiator and (a-3) a photopolymerizable monomer and is characterized in that the (a-3) component is <10 mass% of the total amount of the (a-1) component and the (a-3) component.

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